



LIST OF REFERENCES CITED BY APPLICANT

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ATTY. DOCKET NO.

8317-091-999

APPLICATION NO.

09/903,064

APPLICANT

Small, et al.

FILING DATE

July 10, 2001

RECEIVED

GROUP
1-751

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
AA	6,048,406	4/11/00	Misra et al.	134	175		
AB	5,981,454	11/9/99	Small	510	175		
AC	5,972,862	10/26/99	Torii et al.	510	175		
AD	5,885,477	3/23/99	Rasmussen et al.	252	79.2		
AE	5,792,274	8/11/98	Tanabe et al.	134	1.3		
AF	5,709,756	1/20/98	Ward et al.	134	1.3		
AG	5,705,089	1/6/98	Sugihara et al.	252	79.1		
AH	5,672,577	9/30/97	Lee	510	175		
AI	5,645,737	7/8/97	Robinson et al.	216	99		
AJ	5,630,904	5/20/97	Aoyama et al.	438	669		
AK	5,603,849	2/18/97	Li	216	99		
AL	5,571,447	11/5/96	Ward et al.	510	206		
AM	5,563,119	10/8/96	Ward	510	176		
AN	5,560,857	10/1/96	Sakon et al.	510	175		
AO	5,181,985	1/26/93	Lampert et al.	156	635		
AP	5,129,955	7/14/92	Tanaka	134	2		
AQ	4,770,713	9/13/88	Ward	134	38		
AR	4,744,834	5/17/88	Haq	134	38		
AS	4,508,591	4/2/85	Bartlett et al.	156	659.1		
AT	4,428,871	1/31/84	Ward et al.	252	542		
AU	4,403,029	9/6/83	Ward, Jr. et al.	430	258		
AV	4,401,747	8/30/83	Ward, Jr. et al.	430	258		
AW	4,395,479	7/26/83	Ward et al.	430	258		
AX	3,592,773	7/13/71	Muller	252	79.3		

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
AY	EP 0 662 705 B1	8/23/00	EPO					
AZ	WO 98/36045	8/20/98	PCT					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

BA	P.J. Ireland, "High Aspect Ratio Contacts: A Review of the Current Tungsten Plug Process," Thin Solid Films 304 (1997), pp. 1-12.
BB	C. Lee and S.C. Lee, "Effects of Plasma Treatments on the Erosion of TEOS-BPSG Films by Chemical Etchants," Solid State Electronics, Vol. 41, No. 6, pp. 921-923 (1997).
BC	M.R. Baklanov, et al., "Applicability of HF Solutions for Contact Hole Cleaning on Top of SiO_2 ," Electrochemical Society Proceedings, Vol. 97-35, pp. 602-609 (1998).
BD	C. Rafols, et al., "Ionic Equilibria in Aqueous Organic Solvent Mixtures: The Equilibria of HF in an Ethanol + Water Mixture Used for Cleaning Up Semiconductors," J. Electroanalytical Chem. 433, pp. 77-83 (1997).
BE	K. Ueno, et al., "Cleaning of CHF_3 Plasma-Etched $\text{SiO}_2/\text{SiN}/\text{Cu}$ Via Structures with Dilute Hydrofluoric Acid Solutions," J. Electrochem. Soc., Vol. 144, No. 7, pp. 2565-2572 (July 1997).
BF	T. Kujime, et al., "The Cleaning of Particles From Si Water Surface by Fluorine Solution Excited by Megasonic," Proceedings of the 1996 Semi. Pure Water and Chemicals, pp. 245-256 (1996).
BG	P. Singer, "Wafer Cleaning: Making the Transition to Surface Engineering," Semiconductor Int'l, p. 88-92 (Oct. 1995).
BH	M. Liehr and S.R. Kasi, "HF and UV-Ozone Integrated Wafer Preclean: Chemistry and Effects on Thermal Gate Oxide," 1991 Int'l Conf. on Solid State Devices and Materials, Yokohama, pp. 484-486 (1991).
BI	L.O. Ohman and S. Sjöberg, "Equilibrium and Structural Studies of Silicon(IV) and Aluminum(III) in Aqueous Solution. Part 9. A Potentiometric Study of Mono- and Poly-nuclear Aluminum(III) Citrates," J. Chem. Soc. Dalton Trans., pp. 2513-2517 (1983).

EXAMINER

DATE CONSIDERED

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						U.S. PATENT DOCUMENTS					
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE				
<i>[Signature]</i>		5,928,430	7/27/99	Ward et al.							
FOREIGN PATENT DOCUMENTS											
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION				
							YES	NO			
OTHER REFERENCES <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>											
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